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PATENT
5298-05700/PM01016
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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:
Collier et al.

Serial No. 09/899,871

Filed: July 6, 2001

For: METHOD AND SYSTEM FOR
CLEANING A POLISHING PAD

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Group Art Unit: 3723
Examiner: Wilson, L.

Atty. Dkt. No. 5298-05700

I hereby certify that this correspondence is being deposited with the U.S. Postal Service with sufficient postage as First Class Mail in an envelope addressed to: **Box: Non-Fee Amendment**, Commissioner for Patents, Washington, D.C. 20231, on the date indicated below:

February 13, 2003
Date

[signature]
Kevin L. Daffer

AMENDMENT; RESPONSE TO OFFICE ACTION DATED NOVEMBER 20, 2002

Box: Non-Fee Amendment
Commissioner for Patents
Washington, D.C. 20231

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FEB 25 2003

TECHNOLOGY CENTER R3700

Dear Sir/ Madam:

This paper is submitted in response to the Office Action dated November 20, 2002 to further highlight reasons why the application is in condition for allowance.

IN THE SPECIFICATION

Please replace pg. 4, lines 9-25, with the amended paragraph below. A "marked-up" version of each amendment is including in **Attachment A**.

al
In order to increase the effectiveness of a polishing pad in a polishing system, the polishing pad may be cleaned periodically. Such a process is typically a sporadic manual process which involves shutting down the polishing system and depositing water upon the pad in an effort to suspend the particles in solution and subsequently wash them away. Unfortunately, such a process typically does not remove all